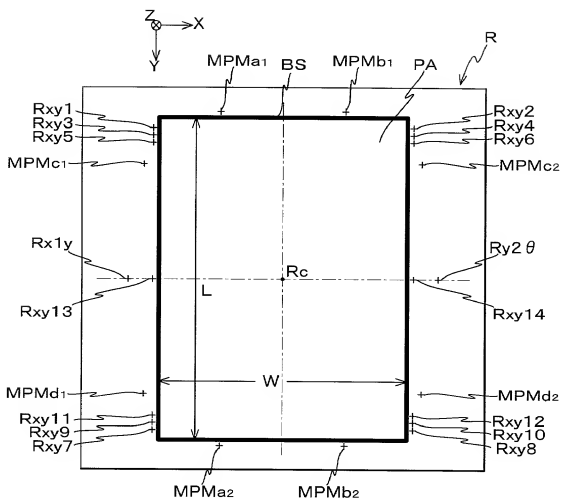


Fig. 1

Fig. 1 is a schematic diagram of a lithographic apparatus. The diagram shows a cross-section of the system with various components labeled. At the top, a coordinate system indicates the X (horizontal), Y (vertical), and Z (depth) directions. The main body of the apparatus is labeled 10. A light source or illumination system (ILU) is shown on the left, directing light towards a series of mirrors (RA1, RA2) and a lens system (R, PL, ALG). The light then passes through a mask (W) and is focused onto a substrate (54). The substrate is supported by a stage (56) and a base (42). A focus monitor (FM) is positioned to monitor the focus of the light on the substrate. Other components labeled include 20, 22, 24, 27, 31, 36a, 36b, 40a, 40b, 52, 58, 60, 62, 74, and 76. A dashed line indicates a specific region of interest.

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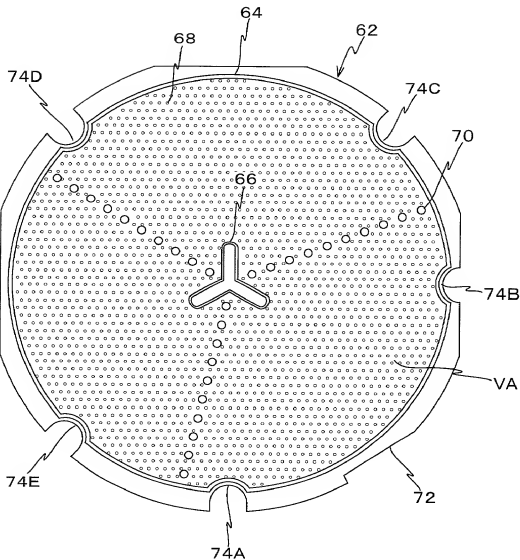
Fig. 3



00000171-070501
 10000171-070501

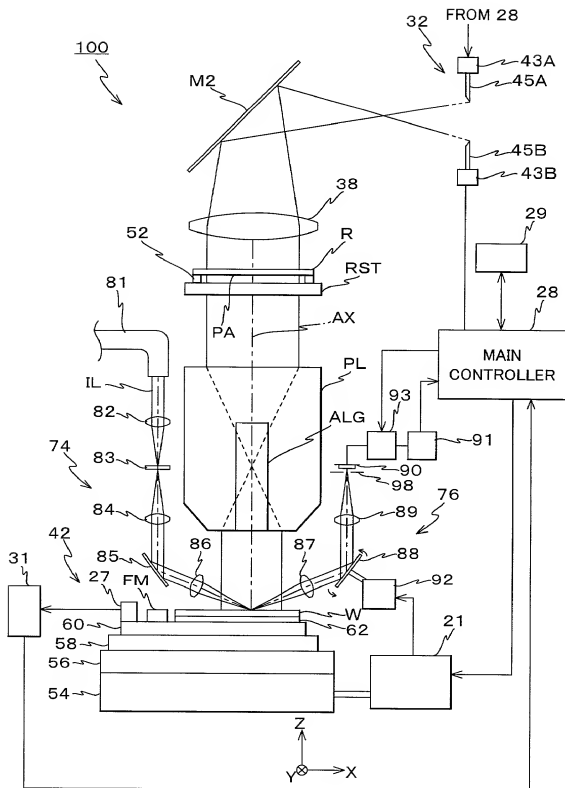
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Fig. 4

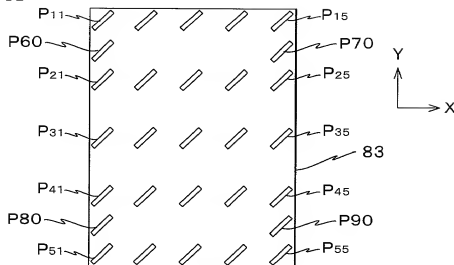


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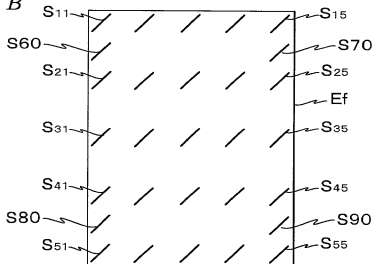
Fig. 5



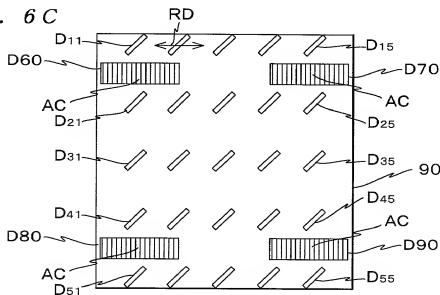
F i g. 6 A



F i g. 6 B



F i g. 6 C



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Fig. 7A

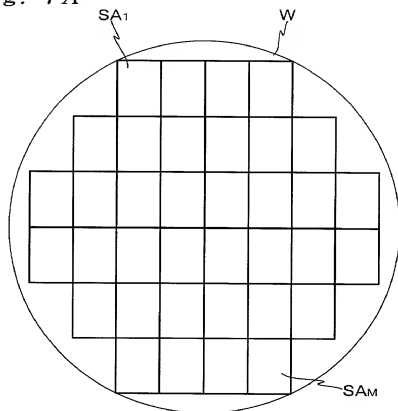
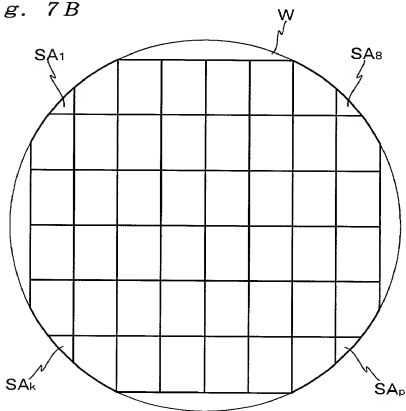


Fig. 7B



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Fig. 8A

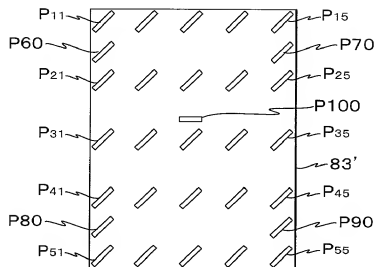


Fig. 8B

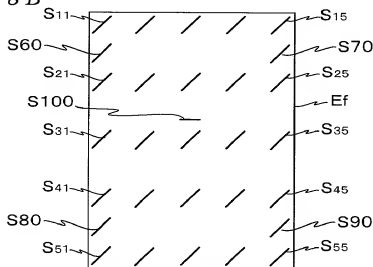


Fig. 8C

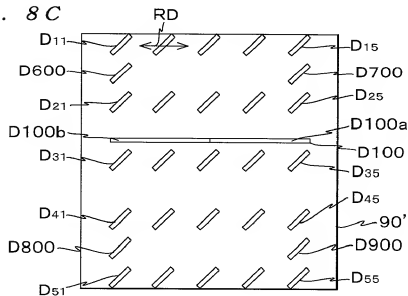
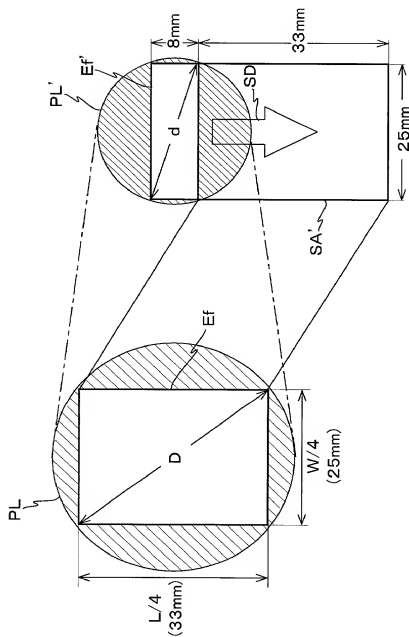
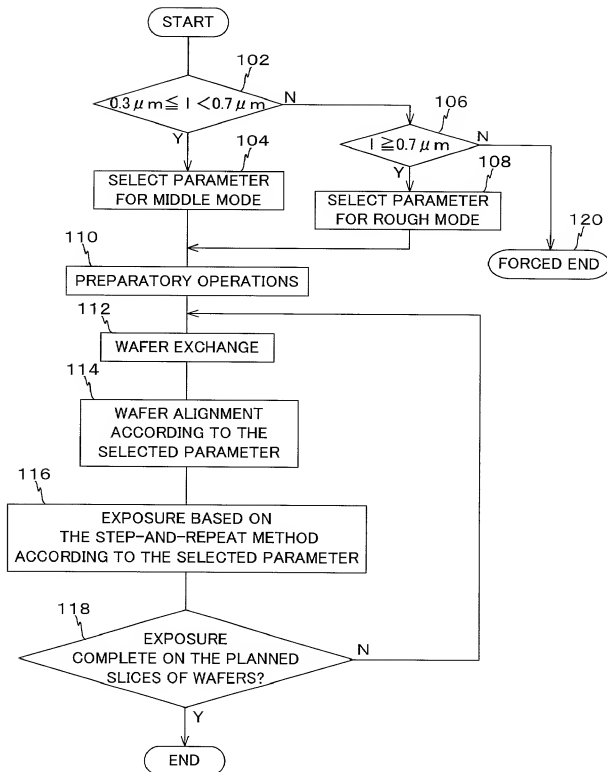


Fig. 9



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Fig. 10

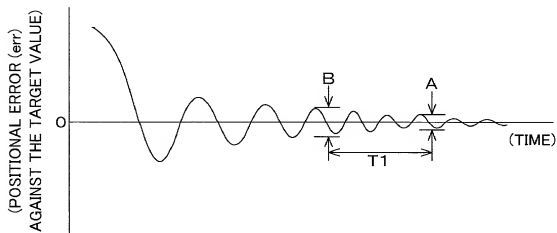


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Fig. 11

MINIMUM LINE WIDTH SUBJECT TO EXPOSURE I	$0.3 \mu\text{m} \leq I < 0.7 \mu\text{m}$	$0.7 \mu\text{m} \leq I$
X, Y PERMISSIBLE VALUES	$\pm 0.1 \mu\text{m}$	$\pm 1 \mu\text{m}$
Z PERMISSIBLE VALUE	$\pm 0.1 \mu\text{m}$	$\pm 1 \mu\text{m}$
NUMBER OF SCREENS FOR ALIGNMENT MEASUREMENT	5	1
NUMBER OF SAMPLE SHOTS	12	3

Fig. 12



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Fig. 13

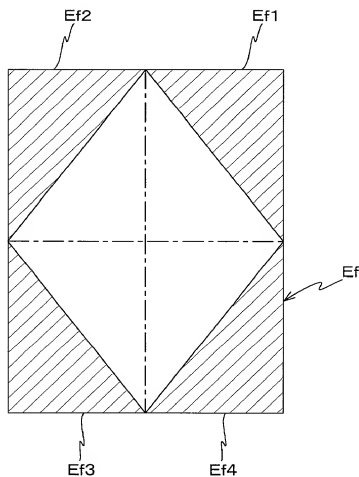
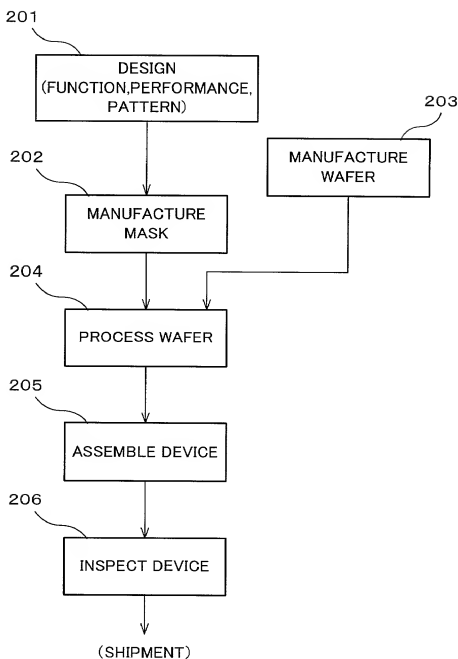


FIG. 13

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Fig. 14



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Fig. 15

